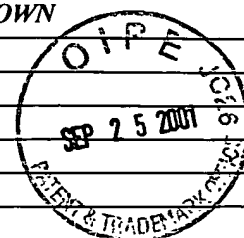


Substitute for form 1449A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(use as many sheets as necessary)**COMPLETE IF KNOWN**

Application Number	09/888,002
Confirmation Number	9049
Filing Date	June 21, 2001
First Named Inventor	Whonchee Lee
Group Art Unit	3723
Examiner Name	



Sheet	1	of	1	Attorney Docket No.	108298515US3
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*EXAMINER INITIALS	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

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EXAMINER

DATE CONSIDERED

11-27-2002

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).